

# Radio frequency-driven proton source with a back-streaming electron dump<sup>a)</sup>

Q. Ji,<sup>1,b)</sup> A. Sy,<sup>1,2</sup> and J. W. Kwan<sup>1</sup>

<sup>1</sup>Lawrence Berkeley National Laboratory, 1 Cyclotron Road, MS 5R0121, Berkeley, California 94720, USA

<sup>2</sup>Department of Nuclear Engineering, University of California, Berkeley, California 94720, USA

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This article describes an rf ion source with a back-streaming electron dump. A quartz tube, brazed to a metal plug at one end, is fused in the center of a flat quartz plate. rf power (at 13.6 MHz) is coupled to generate hydrogen plasma using a planar external antenna bonded to the window. Bonding the water-cooled rf antenna to the quartz window significantly lowers its temperature. The water-cooled metal plug serves as the back-streaming electron dump. At 1800 W, the current density of extracted hydrogen ions reaches approximately 125 mA/cm<sup>2</sup>. © 2010 American Institute of Physics. [doi:10.1063/1.3267832]

## I. INTRODUCTION

Different antenna configurations have been used in rf-driven ion sources: internal antenna,<sup>1</sup> external helical antenna,<sup>2,3</sup> and external planar antenna.<sup>4</sup> Lifetime has always been an issue for internal antenna. Ion sources with external planar antenna produce high-density plasma and exhibit long lifetime, but the dielectric window used as the back plate in the ion source is vulnerable to back-streaming electron bombardment. An ion source with an innovative rf window design has been built at Lawrence Berkeley National Laboratory. A quartz tube, brazed to a metal plug at one end, is fused in the center of the rf window. The water-cooled metal plug serves as the back-streaming electron dump.

## II. RF-DRIVEN ION SOURCE WITH A BACK-STREAMING ELECTRON DUMP

### A. Ion source design

A schematic drawing of the source is shown in Fig. 1(a). The ion source has a 10-cm ID, 6-cm-tall chamber with an air-cooled quartz window at the back. rf power (at 13.6 MHz) is coupled to the plasma using a planar external antenna at the window. Water-cooled permanent magnets are embedded in the cylindrical wall to create the “multicusp” magnetic configuration for improved plasma confinement. The wall material is aluminum. The quartz window is o-ring sealed directly to the chamber wall. A quartz tube, brazed to a metal plug at one end, is fused in the center of the rf window. The water-cooled metal plug serves as the back-streaming electron dump. As seen from the photograph of the source in operation in Fig. 1(b), plasma was localized in the main source chamber. Minimal plasma diffused to the quartz tube with electron dump.

### B. Optimization of rf antenna

Copper tubing has been used as rf antenna to couple rf signal into the plasma chamber. Different sizes of copper tubing with various turns have been compared. Figure 2 shows the extracted ion beam current density from the source with 1/8-in.-diameter and 3/16-in.-diameter copper tubing. The number of turns varied from two and a half to four and a half. With the same size tubing, the ion source with an antenna of higher number of turns produced larger current density. Four and a half turns, 3/16-in.-diameter copper antenna offered the best rf signal coupling to the plasma. The performances of 1/8 in. and 3/16 in. tubing for the same antenna configuration of four and a half turns is similar. The 3/16 in. tubing, however, exhibited several disadvantages: thicker tubing is harder to bend during antenna fabrication, and the thicker tubing resulted in an antenna whose outermost loop closely approached the source chamber wall. When the source was operated at rf power over 1200 W, the plasma was not very stable; this is believed to result from rf coupling into the source chamber. Therefore, in the final design, a copper antenna with 4.5 turns, 1/8 in. tubing was employed. Thermally conductive adhesive (Dow Corning

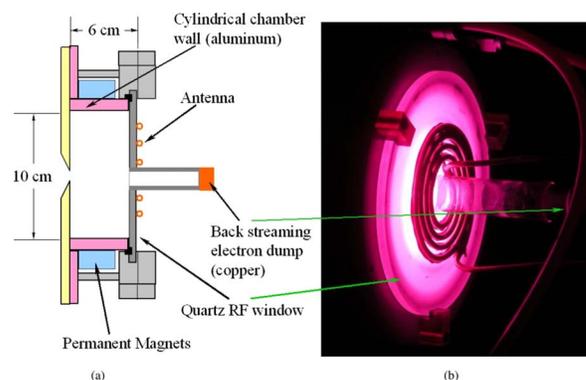


FIG. 1. (Color online) (a) Schematic drawing of the rf ion source with a back-streaming electron dump. (b) A photograph of the ion source in operation.

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<sup>b)</sup> Electronic mail: qji@lbl.gov.

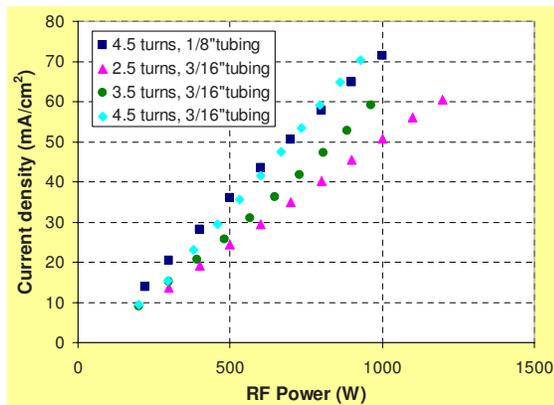


FIG. 2. (Color online) Comparisons of the extracted ion beam current density from ion sources with various types of rf antenna.

1-4173) was used to bond the antenna to the quartz window for improved heat dissipation.

### C. Rf window engineering

Good heat dissipation of the rf window, especially in cw operation mode, helps to prolong source lifetime. Simulations using ANSYS were carried out to analyze the heat distribution on the quartz rf window.

#### 1. ANSYS simulation

Air- and water-cooling at the beam dump were taken into account. Ambient temperature was set at 22 °C. The temperatures at the electron dump and edge of the quartz window were set at 40 and 60 °C, respectively. After plasma

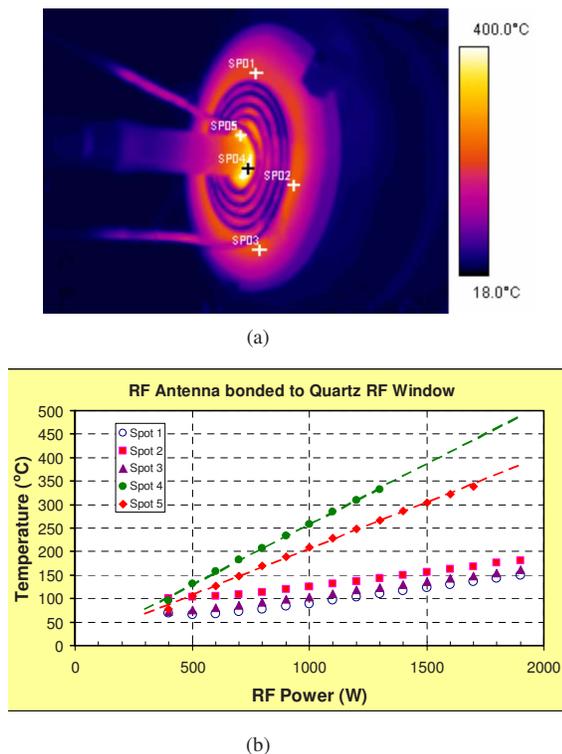


FIG. 3. (Color online) (a) Temperature of the quartz window measured using a ThermoVision™ A20 M infrared camera. (b) Temperatures of spots 1–5 on the quartz rf window bonded to the water-cooled rf antenna, as labeled in (a), increase as rf power increases.

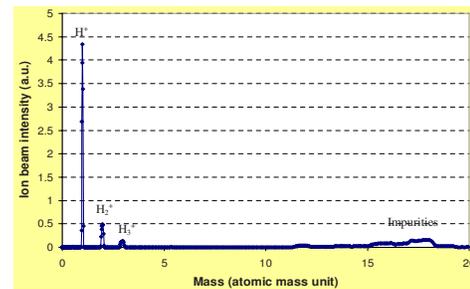


FIG. 4. (Color online) Mass spectrum of hydrogen plasma generated in the source at rf power of 500 W and source pressure of 9 mTorr.

ignition, it was assumed that all rf power was evenly dissipated as heat through all surfaces of the plasma chamber, including the quartz window, source wall, and plasma electrode. In the case of 2000 W of rf input power, the heat load on the quartz window was approximately 7.5 W/cm<sup>2</sup>. Figure 3 shows the heat distribution on the quartz rf window when operated at rf power of 2000 W. When the rf antenna is in loose contact with the quartz window, the temperature at the side facing the plasma can reach as high as 850 °C. Bonding the water-cooled rf antenna to the quartz window helps to dissipate heat quickly and more evenly, significantly lowering the window temperature. According to the simulation result, the “hotspot” is located at the center of the rf window, on the side facing the plasma. At 2000 W, the temperature of the hotspot is reduced to 450 °C through bonding of the antenna to the window. The outer surface was kept rather “cool,” with temperatures around 150 °C.

#### 2. Measured temperature of quartz rf window

Temperature of the quartz rf window was measured using ThermoVision™ A20 M infrared camera. Figure 3(a) illustrates the temperature distribution on the quartz window when the ion source was operated at 2000 W, with the rf antenna bonded to the quartz window. Temperatures of five different spots on the quartz window were monitored when rf operating power was increased. Figure 3(b) shows the temperature of spots 1–5 on the quartz window as a function of rf power. Because the maximum measurable temperature of the camera is 350 °C, no data was collected beyond this point; extrapolated temperatures are plotted in Fig. 3(b) as dashed lines.

The “hotspot” shown in the photograph in Fig. 3(a) is in the center of the quartz, around the joints of the quartz plate and tubing where the metal electron dump was brazed on. This corresponds to the hotspot location predicted in the ANSYS simulations. The temperature at the “hotspot” reached around 500 °C, and temperatures near the outermost loop of

TABLE I. Hydrogen ion species fraction vs rf power.

rf power (W)	H <sup>+</sup> (%)	H <sub>2</sub> <sup>+</sup> (%)	H <sub>3</sub> <sup>+</sup> (%)
300	83.0	13.1	3.9
500	87.7	9.7	2.6
1000	91.1	7.9	1.0

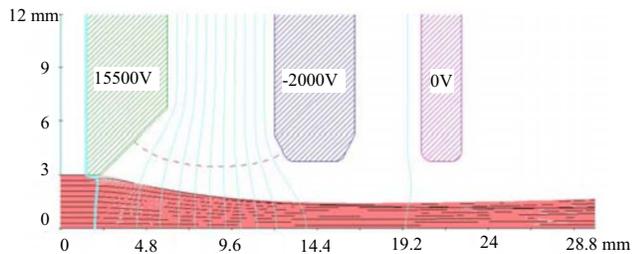


FIG. 5. (Color online) Extraction column and the voltage settings in IGUN-7.030 simulation.

the antenna were below 200 °C; these results are also consistent with the ANSYS simulations.

### III. EXPERIMENTAL RESULTS

#### A. Atomic ion fraction

Hydrogen was used in the experiment. The source was operated at around 9 mTorr. Both atomic  $H^+$  ions and molecular  $H_2^+$  and  $H_3^+$  ions exist in hydrogen plasmas. The mass spectrum of hydrogen plasma generated in this rf-driven ion source has been measured using a magnetic mass spectrometer. Figure 4 shows the mass spectrum of the plasma at rf power of 500 W and source pressure of 9 mTorr. Over 85% of  $H^+$  has been achieved. As listed in Table I, the atomic ion fraction increases with the rf power, and both  $H_2^+$  and  $H_3^+$  fractions decrease as rf power increases.

#### B. Extracted current density

An extraction column with aperture of 6 mm in diameter was designed. The beam trajectories simulated using IGUN-7.030 are shown in Fig. 5. In the experiment, ion beams were extracted through various aperture sizes, from 1 mm to 6 mm in diameter. Different extraction and suppression voltages were used for different rf input power to match the perveance.

The measured current density as a function of rf (13.56 MHz) power is plotted in Fig. 6, with extraction aperture diameters of 1 and 6 mm. The current density extracted from a 6 mm aperture is in agreement with that of a 1 mm aperture, with the 6 mm aperture exhibiting slightly higher extracted beam current density for rf power above 500 W. At 1800 W, the extracted current density reaches approximately

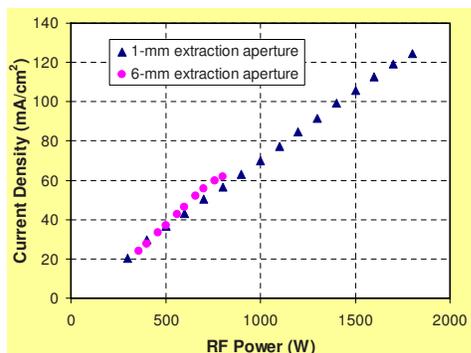


FIG. 6. (Color online) Extracted ion beam current density as a function of input rf power.

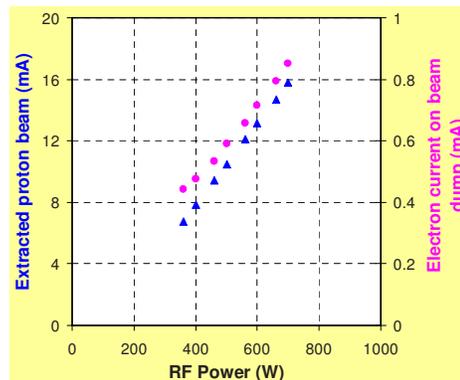


FIG. 7. (Color online) Both extracted proton beam through a 6 mm aperture and back-streaming electron current monitored on the beam dump increase as rf power increases.

125 mA/cm<sup>2</sup>. When a 6-mm-diameter aperture was used, instable beams were observed for rf input power higher than 800 W, the cause of which is still under investigation.

#### C. Electron current measured on beam dump

A back-streaming electron dump was inserted at the quartz rf window to collect back-streaming electrons when extracting positive ions and to prevent the window from damage. In the experiment, a resistor was connected between the electron dump and plasma electrode to monitor the back-streaming electron current. As shown in Fig. 7, both the extracted proton beam and electron current measured on the beam dump increase as rf power increases, and the back-streaming electron beam follows the same trend as the extracted proton beam. Less than 1 mA of back-streaming electrons was measured when 16 mA of protons were extracted through a 6 mm aperture at rf power of 700 W.

### IV. SUMMARY

An rf-driven ion source with a back-streaming electron dump has been fabricated and tested. Bonding water-cooled rf antenna directly to the quartz window significantly lowers the rf window temperature. At 1800 W, the extracted hydrogen current density reaches approximately 125 mA/cm<sup>2</sup>. Over 90% of hydrogen ions have been achieved at rf power of 1000 W.

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<sup>1</sup>Q. Ji, X. Jiang, T.-J. King, K.-N. Leung, K. Standiford, and S. B. Wilde, *J. Vac. Sci. Technol. B* **20**, 2717 (2002).

<sup>2</sup>X. Jiang, Q. Ji, A. Chang, and K.-N. Leung, *Rev. Sci. Instrum.* **74**, 2288 (2003).

<sup>3</sup>S. K. Hahto, S. T. Hahto, Q. Ji, K.-N. Leung, E. L. Foley, L. R. Grisham, and F. M. Levinton, *Rev. Sci. Instrum.* **75**, 355 (2004).

<sup>4</sup>J. H. Vainionpaa, T. Kalvas, S. K. Hahto, and J. Reijonen, *Rev. Sci. Instrum.* **78**, 063503 (2007).